ABSTRACT OF THE DISCLOSURE

An exposure method and an exposure apparatus are disclosed wherein one or more plural sample shot processes are made to a substrate and an exposure process is made to the substrate after completion of the sample shot process or processes. The procedure includes a first determining step for determining the processing order in a first sample shot process, of the plural sample shot processes, and a second determining step for determining the processing order in a second sample shot process to be made after the first sample shot process, wherein, in at least one of the first and second determining steps, the determination is made under a condition that an interval between a shot to be processed last in the first sample shot process and a shot to be processed first in the second sample shot process is shortened.

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